

L Number	Hits	Search Text	DB	Time stamp
9	351249	mask or photomask or reticle	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:45
10	144471	line with width	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:48
11	29793	(mask or photomask or reticle) and (line with width)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
12	27982	10.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
13	2336	((mask or photomask or reticle) and (line with width)) and 10.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
14	451	10.ti.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
16	135207	9.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
17	1480	10.ab. and 9.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
15	66	((mask or photomask or reticle) and (line with width)) and 10.ab.) and 10.ti.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:47
18	53265	line with chip	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:48
19	763	(mask or photomask or reticle) with (line with chip)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:49
20	159	19.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:49
21	282	(line with width) and ((mask or photomask or reticle) with (line with chip))	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:49
22	38	19.ab. and ((line with width) and ((mask or photomask or reticle) with (line with chip)))	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:51
23	1016	across with chip with line	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:51
24	287	(mask or photomask or reticle) and (across with chip with line)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:52
25	99	23.clm.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:52
26	28	((mask or photomask or reticle) and (across with chip with line)) and 23.clm.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:54
27	71	23.clm. not ((mask or photomask or reticle) and (across with chip with line)) and 23.clm.)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:55
28	61164	9.clm.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:54
29	0	(23.clm. not ((mask or photomask or reticle) and (across with chip with line)) and 23.clm.)) and 9.clm.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:55
30	74	(across with chip with line) and 9.clm.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 06:55
31	64	((across with chip with line) and 9.clm.) not ((mask or photomask or reticle) and (across with chip with line)) and 23.clm.)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:08

32	59	aclwv or aclv	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:09
33	43	(mask or photomask or reticle) and (aclwv or aclv)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:09
34	8	32.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:09
35	5	((mask or photomask or reticle) and (aclwv or aclv)) and 32.ab.	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:22
36	418	(phase with shape) same target	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:22
37	35	9.clm. and ((phase with shape) same target)	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:23
38	3	(across with chip with line) and (9.clm. and ((phase with shape) same target))	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:23
39	6	(line with chip) and (9.clm. and ((phase with shape) same target))	USPAT; US-PGPUB; EPO; JPO	2004/11/01 07:24

PALM INTRANET

Day : Monday
 Date : 11/1/2004
 Time : 07:56:14

Inventor Name Search Result

Your Search was:

Last Name = LIEBMANN

First Name = LARS

Application#	Patent#	Status	Date Filed	Title	Inventor Name 49
<u>10920786</u>	Not Issued	020	08/18/2004	METHOD FOR DESIGNING ALTERNATING PHASE SHIFT MASKS	LIEBMANN, LARS W.
<u>10917193</u>	Not Issued	019	08/12/2004	PHYSICAL DESIGN SYSTEM AND METHOD	LIEBMANN, LARS W.
<u>10801880</u>	Not Issued	030	03/16/2004	ALTERNATING PHASE SHIFT MASK DESIGN WITH OPTIMIZED PHASE SHAPES	LIEBMANN, LARS W.
<u>10710224</u>	Not Issued	030	06/28/2004	SYSTEM FOR COLORING A PARTIALLY COLORED DESIGN IN AN ALTERNATING PHASE SHIFT MASK	LIEBMANN, LARS W.
<u>10708535</u>	Not Issued	030	03/10/2004	PLIANT SRAF FOR IMPROVED PERFORMANCE AND MANUFACTURABILITY	LIEBMANN, LARS W.
<u>10708055</u>	Not Issued	030	02/05/2004	METHOD OF CONFLICT AVOIDANCE IN FABRICATION OF GATE-SHRINK ALTERNATING PHASE SHIFTING MASKS	LIEBMANN, LARS W.
<u>10707962</u>	Not Issued	030	01/28/2004	ALTERNATING PHASE SHIFT MASK DESIGN FOR HIGH PERFORMANCE CIRCUITRY	LIEBMANN, LARS W.
<u>10707778</u>	Not Issued	030	01/12/2004	SYSTEM AND METHOD OF SMOOTHING MASK SHAPES FOR IMPROVED PLACEMENT OF SUB-RESOLUTION ASSIST FEATURES	LIEBMANN, LARS W.
<u>10604373</u>	Not Issued	030	07/15/2003	GENERATING MASK PATTERNS FOR ALTERNATING PHASE-SHIFT MASK LITHOGRAPHY	LIEBMANN, LARS W.

<u>10430148</u>	<u>6795961</u>	150	05/06/2003	PRIORITY COLORING FOR VLSI DESIGNS	LIEBMANN, LARS W.
<u>10378579</u>	Not Issued	030	02/28/2003	PITCH-BASED SUBRESOLUTION ASSIST FEATURE DESIGN	LIEBMANN, LARS W.
<u>10378575</u>	Not Issued	030	02/28/2003	BINARY OPC FOR ASSIST FEATURE LAYOUT OPTIMIZATION	LIEBMANN, LARS W.
<u>10300240</u>	Not Issued	030	11/20/2002	PHASE-WIDTH BALANCED ALTERNATING PHASE SHIFT MASK DESIGN	LIEBMANN, LARS W.
<u>10264142</u>	Not Issued	093	10/03/2002	INTEGRATED LITHOGRAPHIC LAYOUT OPTIMIZATION	LIEBMANN, LARS W.
<u>10249317</u>	Not Issued	030	03/31/2003	LAYOUT IMPACT REDUCTION WITH ANGLED PHASE SHAPES	LIEBMANN, LARS W.
<u>10164242</u>	Not Issued	094	06/05/2002	SELF-ALIGNED ALTERNATING PHASE SHIFT MASK PATTERNING PROCESS	LIEBMANN, LARS W.
<u>10014707</u>	<u>6757886</u>	150	11/13/2001	ALTERNATING PHASE SHIFT MASK DESIGN WITH OPTIMIZED PHASE SHAPES	LIEBMANN, LARS W.
<u>09997657</u>	<u>6609245</u>	150	11/29/2001	PRIORITY COLORING FOR VLSI DESIGNS	LIEBMANN, LARS W.
<u>09774742</u>	Not Issued	161	01/31/2001	OPTICAL PROXIMITY CORRECTION (OPC) USING AUTOMATED SHAPE AND EDGE PRE-SORTING	LIEBMANN, LARS W.
<u>09759013</u>	<u>6578190</u>	150	01/11/2001	PROCESS WINDOW BASED OPTICAL PROXIMITY CORRECTION OF LITHOGRAPHIC IMAGES	LIEBMANN, LARS W.
<u>09754920</u>	<u>6602728</u>	150	01/05/2001	METHOD FOR GENERATING A PROXIMITY MODEL BASED ON PROXIMITY RULES	LIEBMANN, LARS W.
<u>09754910</u>	<u>6553559</u>	150	01/05/2001	METHOD TO DETERMINE OPTICAL PROXIMITY CORRECTION AND ASSIST FEATURE RULES WHICH ACCOUNT FOR VARIATIONS IN MASK DIMENSIONS	LIEBMANN, LARS W.
<u>09566885</u>	<u>6338922</u>	150	05/08/2000	OPTIMIZED ALTERNATING PHASE SHIFTED MASK DESIGN	LIEBMANN, LARS W.
<u>09460034</u>	<u>6421820</u>	150	12/13/1999	SEMICONDUCTOR DEVICE	LIEBMANN,

				FABRICATION USING A PHOTOMASK WITH ASSIST FEATURES	LARS W.
<u>09325473</u>	Not Issued	161	06/03/1999	METHOD AND APPARATUS FOR ENHANCED EFFICIENCY PROXIMITY CORRECTION	LIEBMANN , LARS W.
<u>09301778</u>	<u>6277527</u>	150	04/29/1999	METHOD OF MAKING A TWIN ALTERNATING PHASE SHIFT MASK	LIEBMANN , LARS W.
<u>09268414</u>	<u>6066180</u>	150	03/15/1999	AUTOMATIC GENERATION OF PHASE SHIFT MASKS USING NET COLORING	LIEBMANN , LARS W.
<u>09250909</u>	<u>6055367</u>	150	02/16/1999	SEMICONDUCTOR DEVICE COMPENSATION SYSTEM AND METHOD	LIEBMANN , LARS WOLFGANG
<u>09127741</u>	<u>5936738</u>	150	08/03/1998	FOCUS MONITOR FOR ALTERNATING PHASE SHIFTED MASKS	LIEBMANN , LARS W.
<u>09103896</u>	Not Issued	161	06/24/1998	SEMICONDUCTOR DEVICE AND MANUFACTURING METHOD	LIEBMANN , LARS
<u>09028833</u>	<u>5932377</u>	150	02/24/1998	EXACT TRANSMISSION BALANCED ALTERNATING PHASE-SHIFTING MASK FOR PHOTOLITHOGRAPHY	LIEBMANN , LARS W.
<u>09005613</u>	<u>6083275</u>	150	01/09/1998	OPTIMIZED PHASE SHIFT DESIGN MIGRATION	LIEBMANN , LARS W.
<u>08884862</u>	<u>5899706</u>	150	06/30/1997	METHOD OF REDUCING LOADING VARIATION DURING ETCH PROCESSING	LIEBMANN , LARS
<u>08824700</u>	<u>6057063</u>	150	04/14/1997	PHASE SHIFTED MASK DESIGN SYSTEM, PHASE SHIFTED MASK AND VLSI CIRCUIT DEVICES MANUFACTURED THEREWITH	LIEBMANN , LARS W.
<u>08823576</u>	<u>5923566</u>	150	03/25/1997	PHASE SHIFTED DESIGN VERIFICATION ROUTINE	LIEBMANN , LARS W.
<u>08810844</u>	<u>5883813</u>	150	03/04/1997	AUTOMATIC GENERATION OF PHASE SHIFT MASKS USING NET COLORING	LIEBMANN , LARS W.
<u>08783631</u>	<u>5795685</u>	150	01/14/1997	SIMPLE REPAIR METHOD FOR PHASE SHIFTING MASKS	LIEBMANN , LARS W.
<u>08781401</u>	<u>5877964</u>	150	01/10/1997	SEMICONDUCTOR DEVICE COMPENSATION SYSTEM AND METHOD	LIEBMANN , LARS WOLFGANG

<u>08740598</u>	<u>5807649</u>	150	10/31/1996	LITHOGRAPHIC PATTERNING METHOD AND MASK SET THEREFOR WITH LIGHT FIELD TRIM MASK	LIEBMANN, LARS W.
<u>08733584</u>	<u>5923562</u>	150	10/18/1996	A METHOD FOR AUTOMATICALLY ELIMINATING THREE-WAY INTERSECTION DESIGN CONFLICTS IN PHASE EDGE, PHASE SHIFT DESIGNS	LIEBMANN, LARS W.
<u>08655790</u>	<u>5740068</u>	150	05/30/1996	FIDELITY ENHANCEMENT OF LITHOGRAPHIC AND REACTIVE-ION-ETCHED IMAGES BY OPTICAL PROXIMITY CORRECTION	LIEBMANN, LARS W.
<u>08570851</u>	<u>6185727</u>	150	12/12/1995	DESIGN VERIFICATION FOR ASYMMETRIC PHASE SHIFT MASK LAYOUTS	LIEBMANN, LARS W.
<u>08470728</u>	<u>5553274</u>	150	06/06/1995	VERTEX MINIMIZATION IN A SMART OPTICAL PROXIMITY CORRECTION SYSTEM	LIEBMANN, LARS W.
<u>08444471</u>	<u>5671152</u>	150	05/19/1995	EFFICIENT GENERATION OF NEGATIVE FILL SHAPES FOR CHIPS AND PACKAGES	LIEBMANN, LARS W.
<u>08440051</u>	<u>5636131</u>	150	05/12/1995	GEOMETRIC AUTOGENERATION OF "HARD" PHASE-SHIFT DESIGNS FOR VLSI	LIEBMANN, LARS WOLFGANG
<u>08434089</u>	<u>5657235</u>	150	05/03/1995	CONTINUOUS SCALE OPTICAL PROXIMITY CORRECTION BY MASK MAKER DOSE MODULATION	LIEBMANN, LARS W.
<u>08423597</u>	<u>5553273</u>	150	04/17/1995	VERTEX MINIMIZATION IN A SMART OPTICAL PROXIMITY CORRECTION SYSTEM	LIEBMANN, LARS W.
<u>08290625</u>	<u>5537648</u>	150	08/15/1994	GEOMETRIC AUTOGENERATION OF "HARD" PHASE-SHIFT DESIGNS FOR VLSI	LIEBMANN, LARS W.
<u>08285575</u>	<u>5538833</u>	150	08/03/1994	HIGH RESOLUTION PHASE EDGE LITHOGRAPHY WITHOUT THE NEED FOR A TRIM MASK	LIEBMANN, LARS W.

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